S-104.3610 Nanotechnology (5 cr)

You can answer either in English or Finnish. Numerical values of calculations are not needed (calculators not necessary).

- Explain <u>briefly</u> (max. 2 pages altogether, draw schematics if needed):
 - a) basics of EUV lithography
 - b) focused ion beams in nanofabrication
 - c) nanoimprint lithography
 - d) break-junction technique in molecular electronics
 - e) two examples of biomimetic nanostructures
 - f) superhydrophobic surface (each 1 p)
- 2. a) CVD fabrication of carbon nanotubes. (3 p)
 - b) Applications of carbon nanotubes. (3 p)
- 3. a) Nanoelectromechanical (NEMS) sensors using AFM cantilever. (3 p)
 - b) Principle of a single electron transistor (SET). (3 p)
- 4. a) Growth process of atomic layer deposition (ALD). (3 p)
 - b) Importance of high-k oxides in future CMOS transistors. (3 p)
- a) Scanning tunneling microscopy (STM). (3 p)
 - b) An electron in STM tip has an energy of E = 3,5 eV as it tunnels through a V = 7 eV barrier with thickness d to conductive surface. Estimate the change in current if the sample-tip distance is increased from d = 3 Å to 9 Å. Numerical values are not necessary. (3 p)